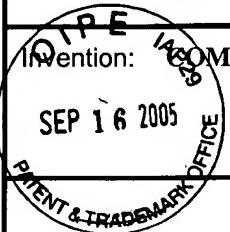


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Invention: COMPOSITION FOR ANTIREFLECTIVE COATING AND METHOD FOR FORMING SAME

SEP 16 2005

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YOKOZUKA TOSHISUKE

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(54) PATTERN FORMING METHOD

(57)Abstract:

PURPOSE: To provide a pattern forming method by which multiple interference of light which becomes an obstacle for fine patterning can be extremely reduced, the manufacturing yield can be improved, and a fine pattern can be effectively formed.

CONSTITUTION: In this pattern forming method, exposure is performed after forming a reflection preventing film on the surface of a photoresist at the time of forming a pattern by photolithography. An amorphous fluorine-bearing polymer is used for forming the reflection preventing film.

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